

**PLASMA REACTOR HAVING RF POWER APPLICATOR AND A DUAL-PURPOSE  
WINDOW**

ABSTRACT OF THE INVENTION

5

In a plasma reactor including a reactor chamber, a workpiece support for holding a workpiece inside the chamber during processing and an inductive antenna, a window electrode proximal a wall of the chamber, the antenna and wall being positioned adjacently, the window electrode being operable as (a) a capacitive electrode accepting RF power to capacitively coupled plasma source power into the chamber, and (b) a window electrode passing RF power therethrough from said antenna into the chamber to inductively couple plasma source power into the chamber.

RECEIVED  
U.S. PATENT OFFICE  
JULY 1978